

**INFORMATION
DISCLOSURE
STATEMENT**

Atty. Docket No.: 150.00880103

Serial No.: 10/045,345

Applicant(s): Derderian et al.

Confirmation No.: 1310

Application Filing Date: 25 October 2001

Group: 2818

Information Disclosure Statement mailed: December 12, 2002

U.S. PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
PD	X	6,337,238	01/08/02	Nakabayashi			

FOREIGN PATENT DOCUMENTS

Examiner Initial	Copy Enclosed	Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
		None						

OTHER DOCUMENTS (Including Authors, Title, Date, Pertinent Papers, etc.)

Examiner Initial	Copy Enclosed	Document Description
		None

RECEIVED
DEC 20 2002
TECHNICAL SERVICES
2600

EXAMINER PHUC T. DANG	Date Considered 7/18/2003
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	

INFORMATION DISCLOSURE STATEMENT	Atty. Docket No.: 150.0088 0103	Serial No.: 10/045,345
	Applicant(s): Derderian et al.	Confirmation No.:
	Filing Date: 25 October 2001	Group: 2818

Examiner Initial	Copy Enclosed	Document Description
PD ↑		Nakamura et al., "Embedded DRAM Technology compatible to the 0.18μm high-speed Logics by using Ru pillars in cell capacitors and peripheral vias," <i>J. Electrochem. Soc.</i> , 147:203-209 (1998).
		Park et al., "Metallorganic Chemical Vapor Deposition of Ru and RuO ₂ Using Ruthenocene Precursor and Oxygen Gas," <i>J. Electrochem. Soc.</i> , 147:203-209 (2000).
		Senzaki et al., Chemical Abstract 128:264103, <i>Proc. Electrochem. Soc.</i> , 97-25 (Chemical Vapor Deposition), 933-43 (1997).
		Shin, "Characterization of RuO ₂ Thin Films Prepared by Hot-Wall Metallorganic Chemical Vapor Deposition," <i>J. Electrochem. Soc.</i> , 144, 1055 (1997).
		Sosinsky et al., "Hydrocarbon Complexes of Ruthenium. Part IV. Cyclic Dienyl Complexes", <i>J. Chem. Soc.</i> , 16-17, 1633-1640 (1975).
		Takagi et al., "RuO ₂ Bottom Electrodes for Ferroelectric (Pb, La)(Zr, Ti)O ₃ Thin Films by Metalorganic Chemical Vapor Deposition", <i>Jpn. J. Appl. Phys.</i> , 34, 4104-4107 (1995).
		Versteeg et al., "Metalorganic Chemical Vapor Deposition By Pulsed Liquid Injection Using An Ultrasonic Nozzle: Titanium Dioxide on Sapphire from Titanium (IV) Isopropoxide," <i>Journal of the American Ceramic Society</i> , 78, 2763-2768 (1995).
		Yuan, "Low-Temperature Chemical Vapor Deposition of Ruthenium Dioxide form Ruthenium Tetroxide: A Simple Approach to High-Purity RuO ₂ Films," <i>Chem. Mater.</i> , 5, 908 (1993).
PD ↓		Yang, Doo Young et al., "Characterization of Ru Electrodes for Ru/(Ba,Sr)TiO ₃ /Ru Capacitors," <i>Ferroelectrics</i> , 1996. ISAF '96: Proceedings of the Tenth IEEE International Symposium on Applications of Ferroelectrics" New York, NY, August 18, 1996; pgs. 515-518.

EXAMINER PHUC T. DANG	Date Considered 7/18/2003
*Examiner: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.	